

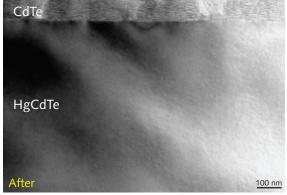
Precision Ion Polishing System (PIPS™)

Model 691

The PIPS™ ion mill is a user-friendly, tabletop Precision Ion Polisher System designed to produce high quality, TEM specimens with large electron transparent areas. The PIPS™ incorporates patented Whisperlok® stage, 2 unique penning ion guns with 10° to -10° milling angles, variable energy milling (down to 100eV), liquid nitrogen specimen cooling and an oil-free vacuum system for ultra-clean specimen processing.

Features B	enefits
Patented pneumatic Whisperlok® stage	No need to vent the chamber to load/unload samples, sample exchange < 1 min
Patented sample holders and loading mechanism	For double sided milling at low angle
2 unique penning ion guns	No consumable parts and lifetime > 30,000 hrs
Beam modulation offering both single and double sector milling	 Minimizes contamination and allows sample cool down High milling rates at shallow angles to less than 1 degree
Variable energy milling: 100eV to 6.0keV	 Minimizes radiation damage and sample heating Produces large and clean electron transparent areas Exceptionally fast milling even at angles below 4 degrees
LN2 specimen cooling	Eliminates artifacts High Throughput - Cool down time 10 minutes (reaches -100 °C) and warm up time (before venting) 10 minutes
CCD camera for "real- time" video monitor imaging (optional)	 Superior fringe enhancement Increases specimen throughput Reduces or eliminates over-milling Reduces specimen handling





Images: LN2 specimen cooling to eliminate artifacts. Image of HgCdTe/CdTe heterostructure sample doped with Hg (80%) and CdTe (20%). Top: Sample prepared at room temperature showing numerous defects in HgCdTe layer. Bottom: Sample prepared in Gatan PIPS™ with cold stage - showing HgCdTe layer completely free of any ion-milling defects. Images courtesy of Dr. Dave Smith and Dr. Changzhen Wang, Arizona State University, AZ, USA.

Specifications	
Ion Source	
Ion Guns	Two Penning ion guns with rare earth magnets
Milling Angle	+10° to -10°, each gun independently adjustable
Ion Beam Energy	100eV to 6.0keV
Beam Diameter	$350\mu m$ FWHM at 5keV - 800 μm FWHM at 5keV for broad beam guns
Ion Current Density	10mA/cm² Peak
Beam Alignment	Precision beam alignment using fluorescent screen
Beam Diameter	Adjustable using gas control
Specimen Stage	
Sample Size	3mm or 2.3mm
Mounting	Gatan patented DuoPost® (standard) or Graphite Holder (optional)
Rotation	Variable from 1 to 6 rpm
Beam Modulation	Single or double sector for exceptional cross-sectioning
Viewing	Binocular microscope 40x or 80x. CCD imaging with 17" LCD monitor 300x - 2200x (optional)
Vacuum	
Dry Pumping System	Two stage diaphragm pump backing a 70 l/sec turbo drag pump
Pressure	5x10 ⁻⁶ torr base pressure, 8x10 ⁻⁵ torr operating pressure
Vacuum Gauge	Cold cathode type for main chamber. Solid-state for backing pump
Specimen Airlock	Gatan Whisperlok®, specimen exchange time < 1 min
Dimensions and Utilities	
Overall Size	560mmW x 480mmD x 430mmH (22"W x 19"D x 17"H)
Shipping Weight	45kg (100lbs)
Power Consumption	200 Watts during operation, 100 Watts with guns off
Power Requirements	Universal 100VAC - 240VAC, 50/60hz (user to specify voltage and frequency)
Gas	Argon gas at 25 psi (1.72 bar)

Note: Specifications are subject to change.

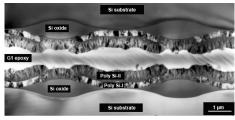
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Ordering information

Model	Description
691	Precision Ion Polishing System (PIPS™)
691.CS	New PIPS™ ion mill with cold stage Whisperlok® and electronic temperature controller
691.CS.UPG	Customer installed upgrade package to add sample cooling to an existing PIPS™

Please consult with your local sales representative for details regarding spares and consumables.

Primary applications



Semiconductor



Metals (oxide)



Metals (alloy)

Images: Semiconductor: Double cross-section of semiconductor sample ion milled with dual beam modulation. Metals (oxide): Cross-section image of a ZnO₂ on sapphire wafer. Metals (alloy): Al-Cu metallization layer thinned on Si substrate. Ceramics: Bulk type ceramic specimen SiC/Al₂O₃.



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Gatan Inc. Corporate Office/ Western USA Sales

5794 W. Las Positas Blvd. Pleasanton, CA 94588 USA tel +1.925.463.0200 fax +1.925.463.0204 info@gatan.com

Eastern USA Sales

780 Commonwealth Dr. Warrendale, PA 15086 USA tel +1.724.776.5260 fax +1.724.776.3360 info@gatan.com

Gatan UK

25 Nuffield Way Abingdon Oxon OX14 1RL United Kingdom tel. +44.0.1235.540160 fax. +44.0.1235.540169 ukinfo@gatan.com

Gatan GmbH

Ingolstädterstr. 12 D-80807 München Germany tel +49 89 358084-0 fax +49 89 358084-77 mfelsmann@gatan.com

Gatan France

3bis, Chemin du Haut Breuil 78113 Grandchamp France tel +33.1.34944407 GSM +33.6.80135139 fax +33.1.34871668 dmonville@gatan.com

Nippon Gatan

3F Sakurai bldg. 2-8-19 Fukagawa, Koto-ku Tokyo 135-0033 Japan tel +81.3.5639.2772 fax: +81.3.5639.2763 rabara@gatan.com

Gatan Singapore

10 Eunos Rd. 8 #12-06 Singapore Post Centre Singapore 408600 tel +1.65.6408.6230 fax +1.65.6293.3307 wchuang@gatan.com